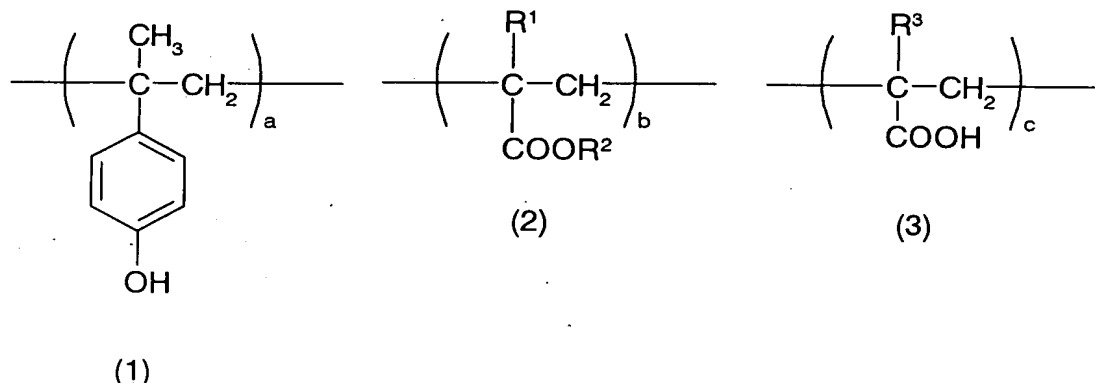


# ABSTRACT OF THE DISCLOSURE

A pattern can be precisely formed by irradiating, with an active energy beam, a positive sensitive resin composition according to this invention comprising a base polymer, an ether-bond-containing olefinic unsaturated compound and an acid-generating agent, where the base polymer is a copolymer comprising the structural units represented by formulas (1) to (3):



where  $\text{R}^1$  and  $\text{R}^3$  are each independently hydrogen or methyl and  $\text{R}^2$  is  $\text{C}_1\text{-C}_6$  straight or branched unsubstituted alkyl or  $\text{C}_1\text{-C}_6$  straight or branched substituted alkyl, wherein a, b and c are 0.05 to 0.7, 0.15 to 0.8 and 0.01 to 0.5, respectively and  $a+b+c=1$ .